MLA150 Quick Start

1. **Transfer design:** Transfer your design file to the tool via Nanofiles FTP
2. **Setup job:** Enter the job **Name** (LastnameFirstinitial_Jobname or Companyname_Jobname) and select the **Exposure Mode**.
3. **Substrate:** Select the **Substrate Template**; there are specific optical and pneumatic templates depending on the substrate size (reference the visual aid at tool).
   **IMPORTANT:** Selecting the wrong template can result in a lens crash!!
4. **Layer:**
   - For First Layer (no alignment): Enter info in the “First Exposure” row.
   - For subsequent layers (with alignment): Enter info into the “2nd Layer” row via [Add Layer].
   - Enter information about the layer being exposed; **Laser Wavelength**, **Laser Power**, **Focus Mode** (must be same as Sub Template).
5. **Converting design:** Follow instructions to convert Design, and Load Design.
6. **Alignment Settings (and Exposure bitmaps):**
   - For exposing alignment marks, use **Exposure Bitmaps** – this option is available if you do not have alignment marks added in your first layer CAD design, the tool can expose Marks for you.
   - **Alignment Settings** allows you to enter coordinates for alignment mark locations used for aligning to previous layers.
7. **Focus Mode:** Set to “Optical” **IMPORTANT** to prevent lens crash! Use Pneumatic only if authorized & it matches your Substrate Template.
8. **Resist:** Always select the “_Generic Focus” resist profile.
9. **HAR** “High Aspect Ratio” is always Off.
10. **Load substrate:**
    - Follow instructions regarding loading the substrate
    - Turn on the stage vacuum
11. **Prior to Exposure:**
    - Make sure all info regarding the job is correct (design, laser, exposure dose, focus, etc.)
12. **Alignment:**
    - Perform alignment to Alignment marks (if needed).
    - [Move to First Cross] and then [Measure] & [Accept Position]
13. **Exposure:** Click “Start Exposure” and wait until the job is complete.
14. **Unloading:** Unload the substrate and enter log book info for your job.